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(54) Title: POLISHING SLURRY, PRODUCTION METHOD OF GLASS SUBSTRATE FOR INFORMATION RECORDING MEDIUM AND PRODUCTION METHOD OF INFORMATION RECORDING MEDIUM

(57) Abstract: The present invention provides a low-cost polishing slurry having excellent effect with respect to defects and smoothness of the surface to be polished. The polishing slurry comprises a silica abrasive and a ceria abrasive, wherein the silica abrasive content is less than 3 mass% and the ceria abrasive content is less than 1 mass%, based on the entire polishing slurry. Further, the present invention provides a method for producing a crystallized glass substrate for an information recording medium, wherein the method use a polishing slurry of the present invention. Furthermore, the present invention provides a method for producing an information recording medium, comprising forming a recording layer on a crystallized glass substrate for an information recording medium obtained by the present method.